

# Leveraging Topographic Etch Selectivity: Atomic Layer Etch Pitch Splitting (APS™)

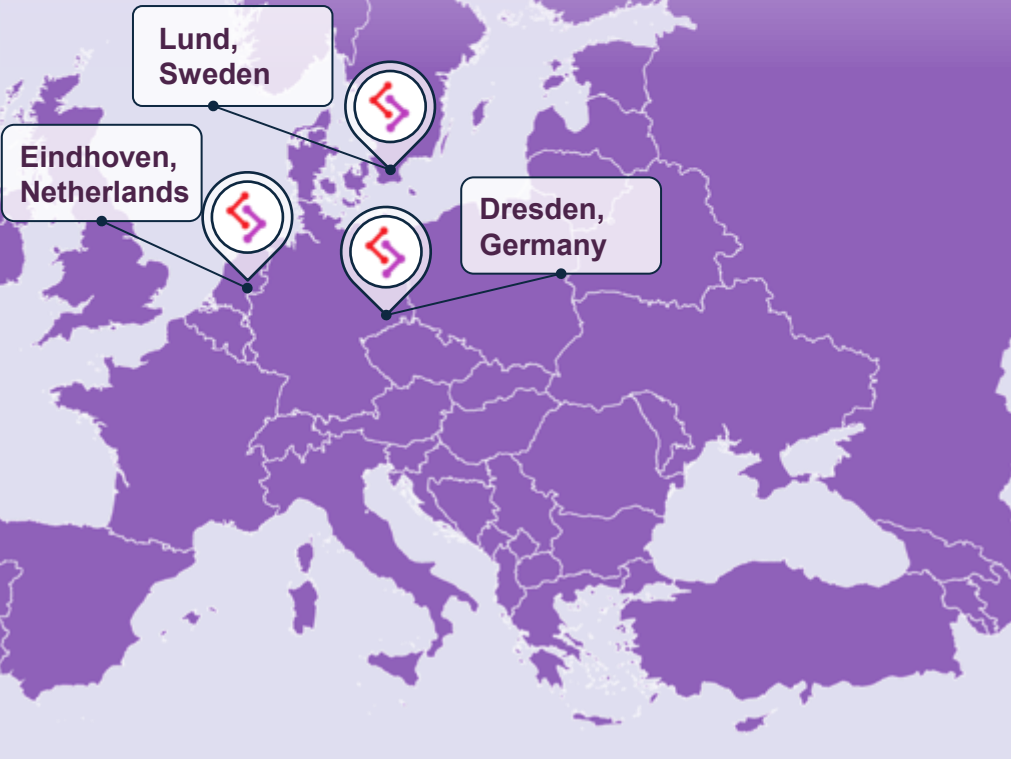
Robin Athle<sup>1</sup>, Reza Jafari Jam<sup>1</sup>, Yoana Ilarionova<sup>1</sup>, Fabian Mathias Veid<sup>1</sup>, Alfred Ahlström Andersson<sup>1</sup>, Svetlana Ivanova<sup>1</sup>, Kishwar Sultana<sup>1</sup>, Asif Muhammad<sup>1</sup>, Mostafa Torbati<sup>1</sup>, Intu Sharma<sup>1</sup>, Hesamedin Safavi<sup>1</sup>, Fred Roozeboom<sup>2</sup>, **Dmitry Suyatin**<sup>1</sup>, Jonas Sundqvist<sup>1</sup>, Amin Karimi<sup>1</sup>

1. AlixLabs AB, Ole Römers Väg 1, Entrance H, 223 63 Lund, Sweden

2. Faculty of Science & Technology, University of Twente, PO Box 217, 7500 AE Enschede, The Netherlands

# AlixLabs AB

- Start-Up & Spin-Off from Lund University
- Founded in Lund, Sweden 2019



## Managed by experts in the ALE and Semiconductor Equipment Industry



### Jonas Sundqvist, PhD

CEO & Co-founder

- Developed ALD and CVD processes since 1999
- Over 25 years of experience in semiconductor manufacturing
- Passionate entrepreneur who delivers on promises
- Strong network in the semiconductor market



### Amin Karimi, PhD

CTO & Co-founder

- Driven to bridge fundamental research and industrial semiconductor applications
- Proven track record in leading R&D projects
- Expert in semiconductor devices, nanofabrication, and materials



### Dmitry Suyatin, PhD

CSO & Co-founder

- Over 25 years of experience in advanced processing of nanostructures
- Author of more than 50 publications
- Well-known ALE expert in the ecosystem



### Per-Anders Eriksson

Deputy CEO and COO

- Business Development
- Semiconductor Equipment industry



### Peo Hansson

Advisor Semi Equipment



### Gary Miner

Advisor Semi Equipment

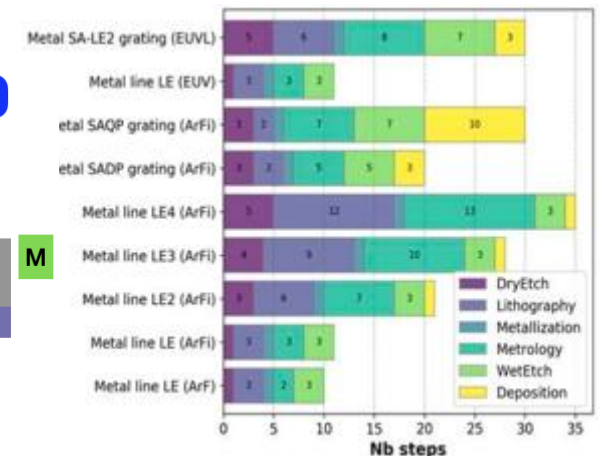
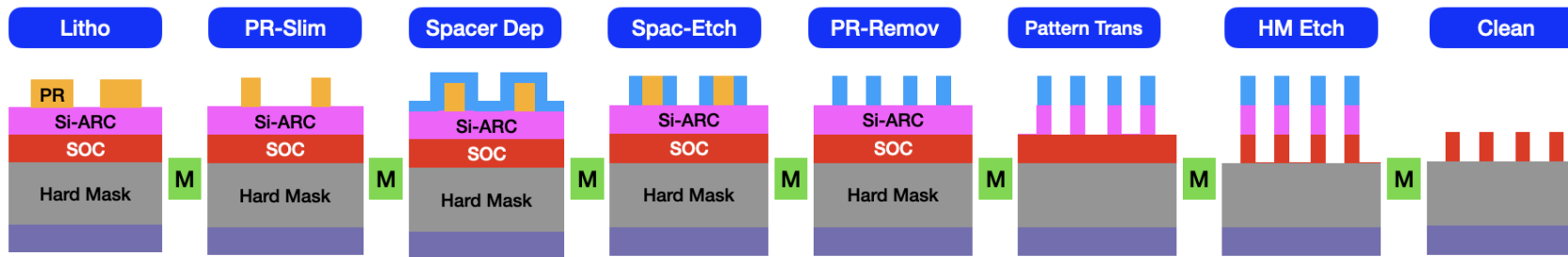
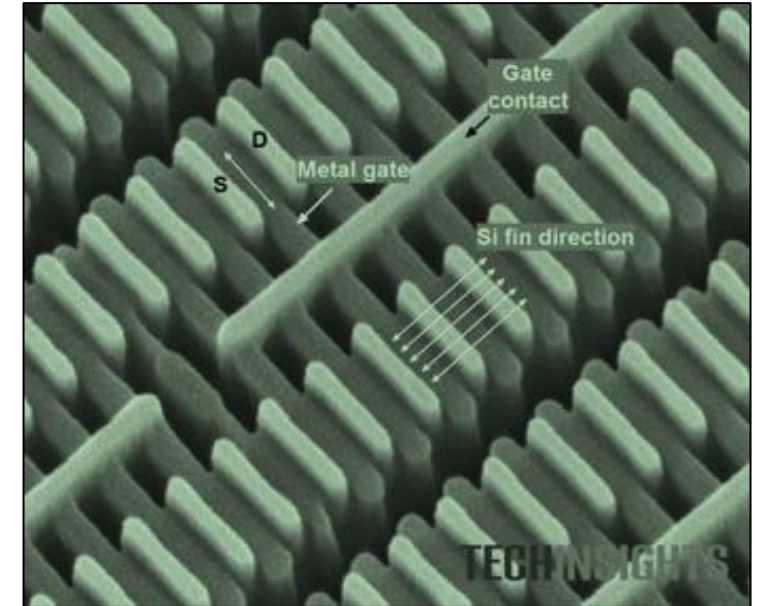
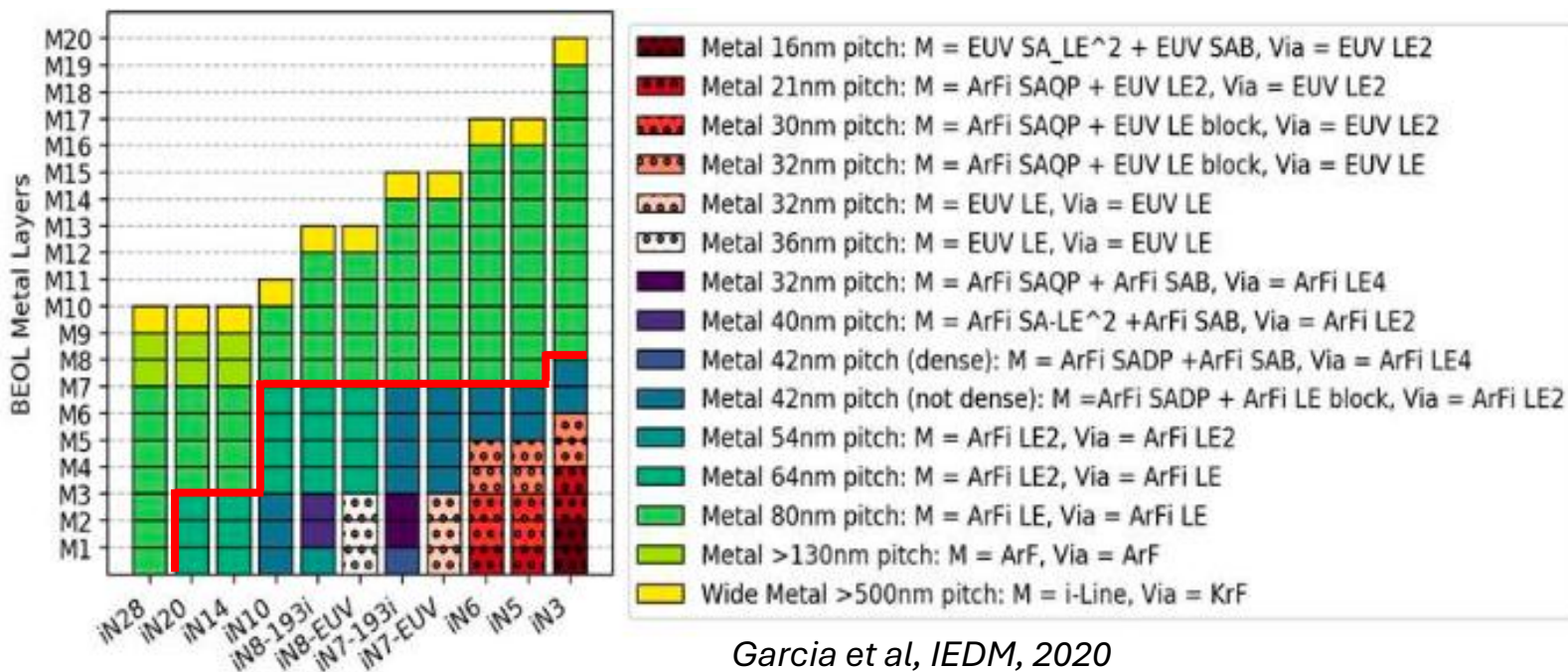


### Robert Cadman,

Advisor Business Development

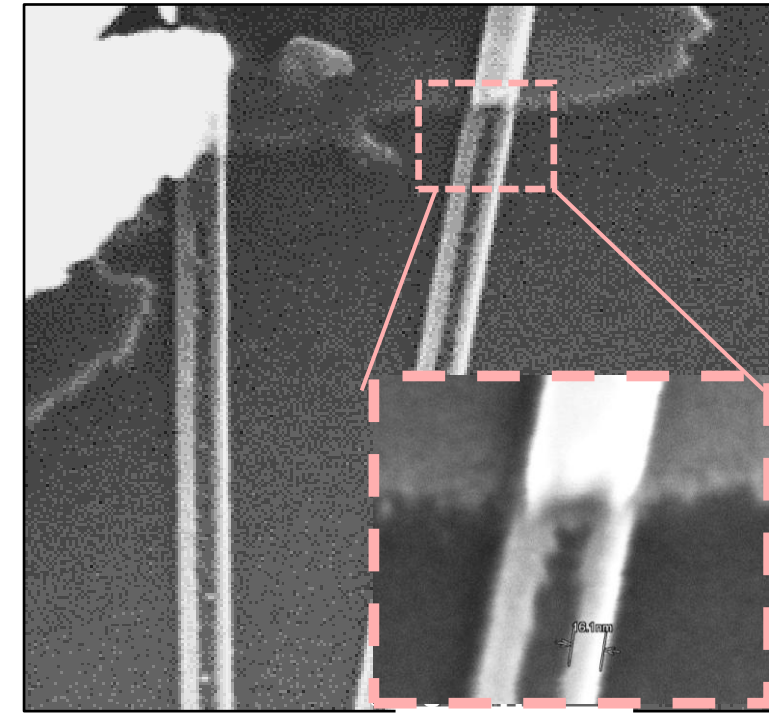
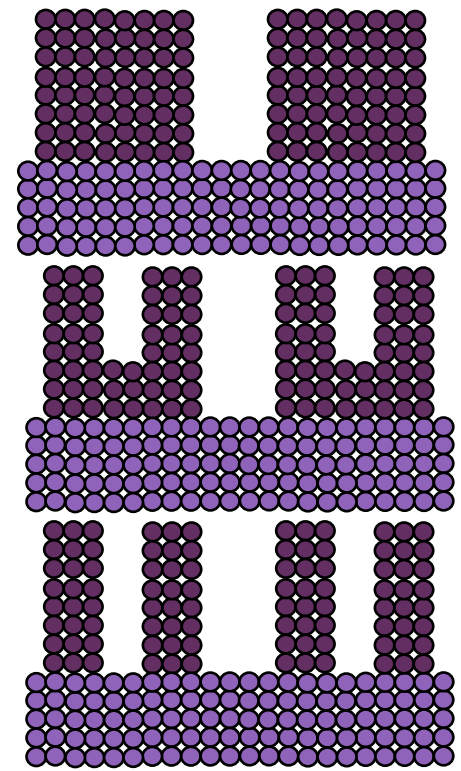
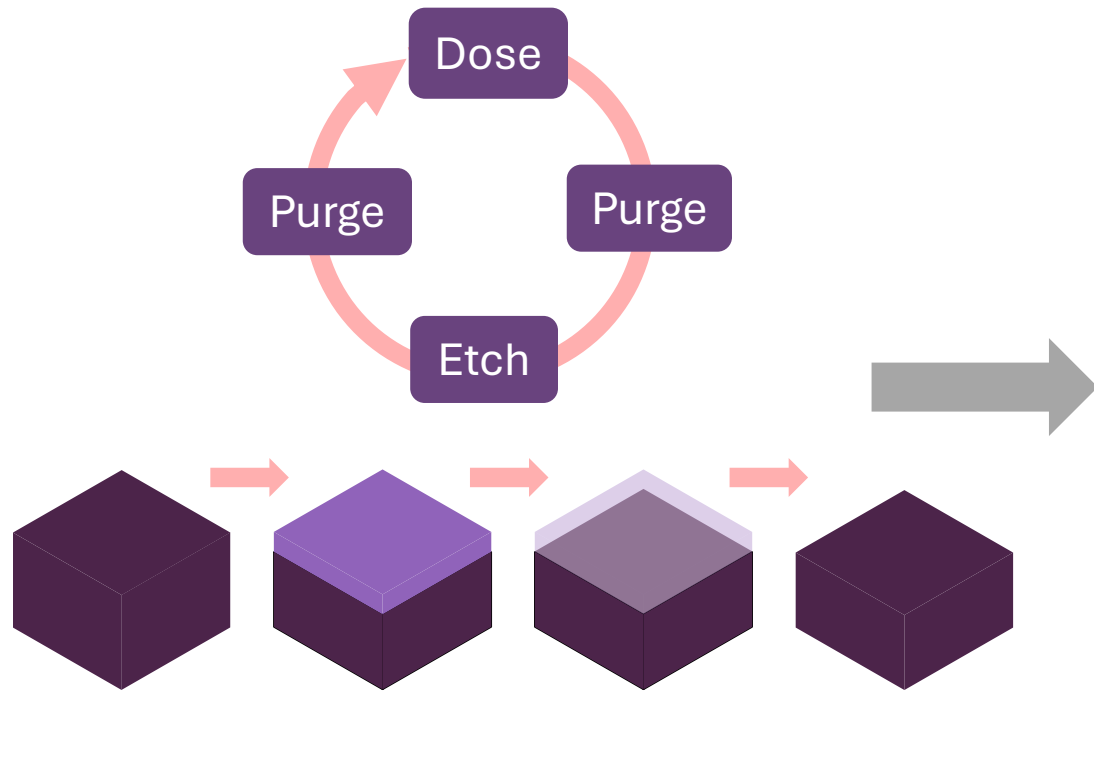


# Dense Line Patterning as a Key Enabler of Moore's Law



*Nakayama et al., Proc. SPIE, 8327, 2012*

# Atomic Layer Etching Pitch Splitting (APS™)



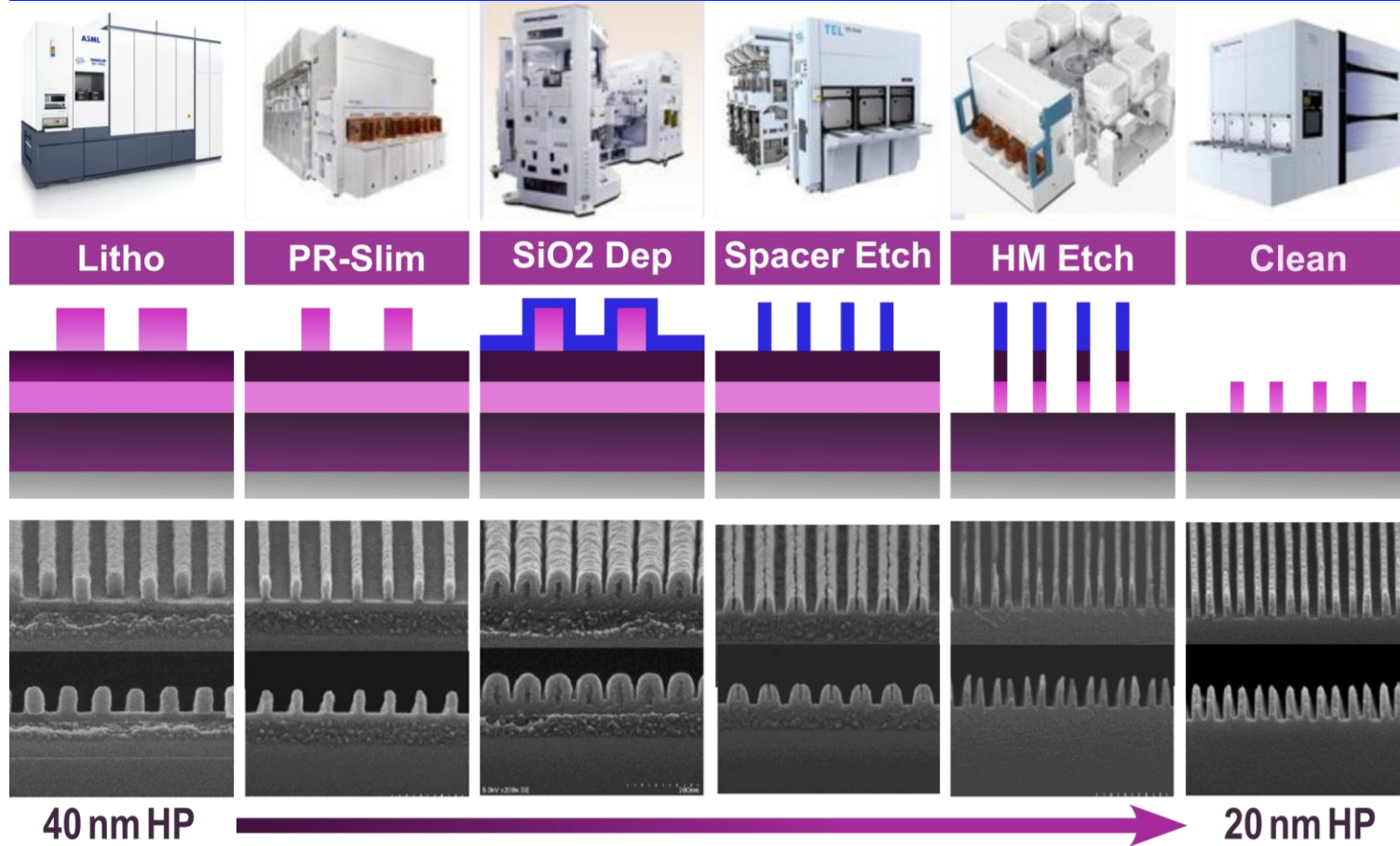
**Atomic Layer Etching (ALE):**  
Surface control using self-limiting chemistries

**Atomic Layer Etch Pitch Splitting (APS™):**  
First demonstration in 2016\* on GaP Nanowires on Si  
\* D. Suyatin et al., 16<sup>th</sup> Int. Conf. on ALD, Dublin, Ireland, July 2016

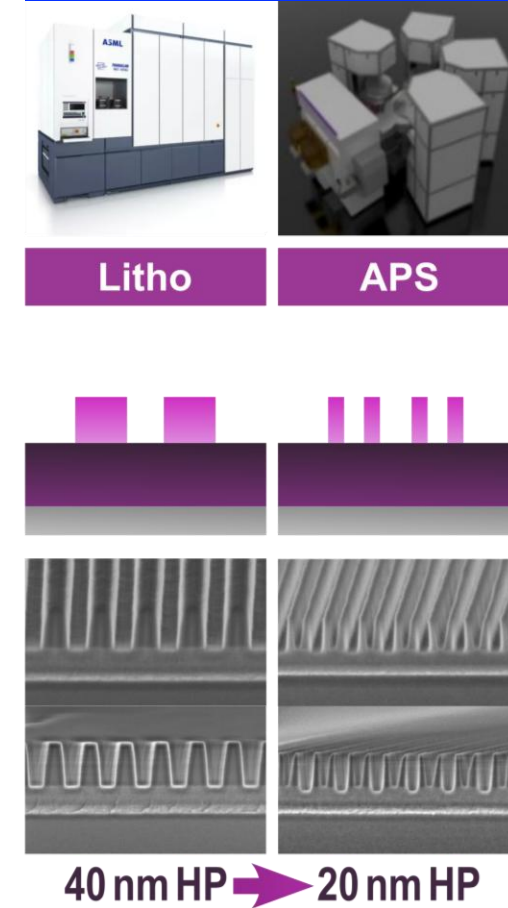
# APS™: – Simplifying advanced patterning – Reducing cost & complexity



## Simplified SADP Process

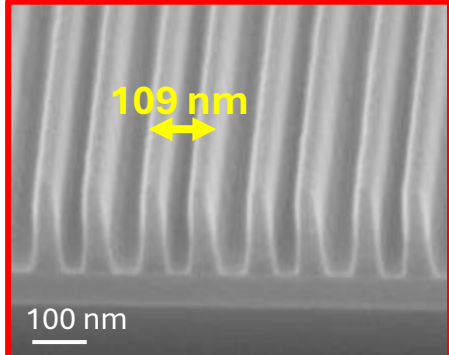
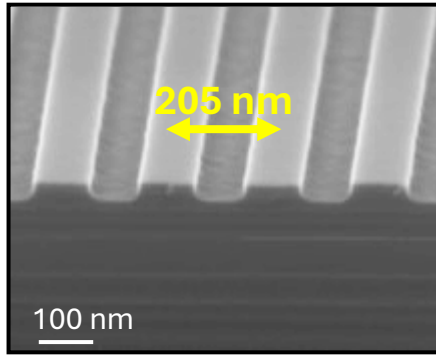
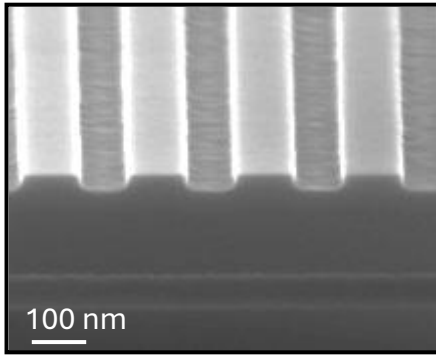
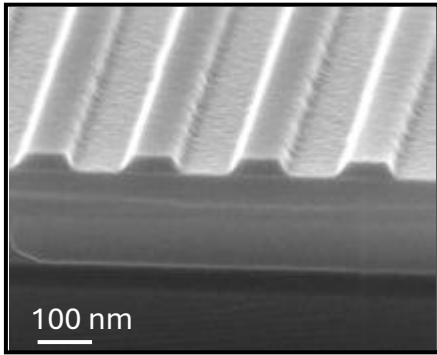
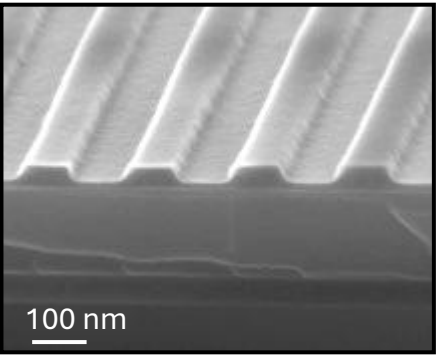
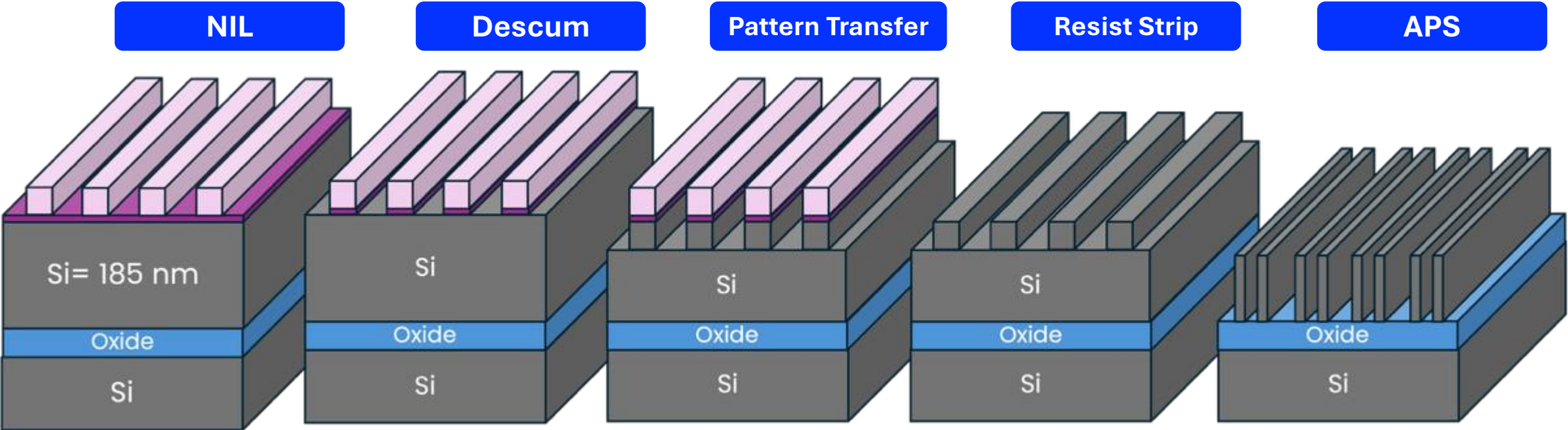


## APS™

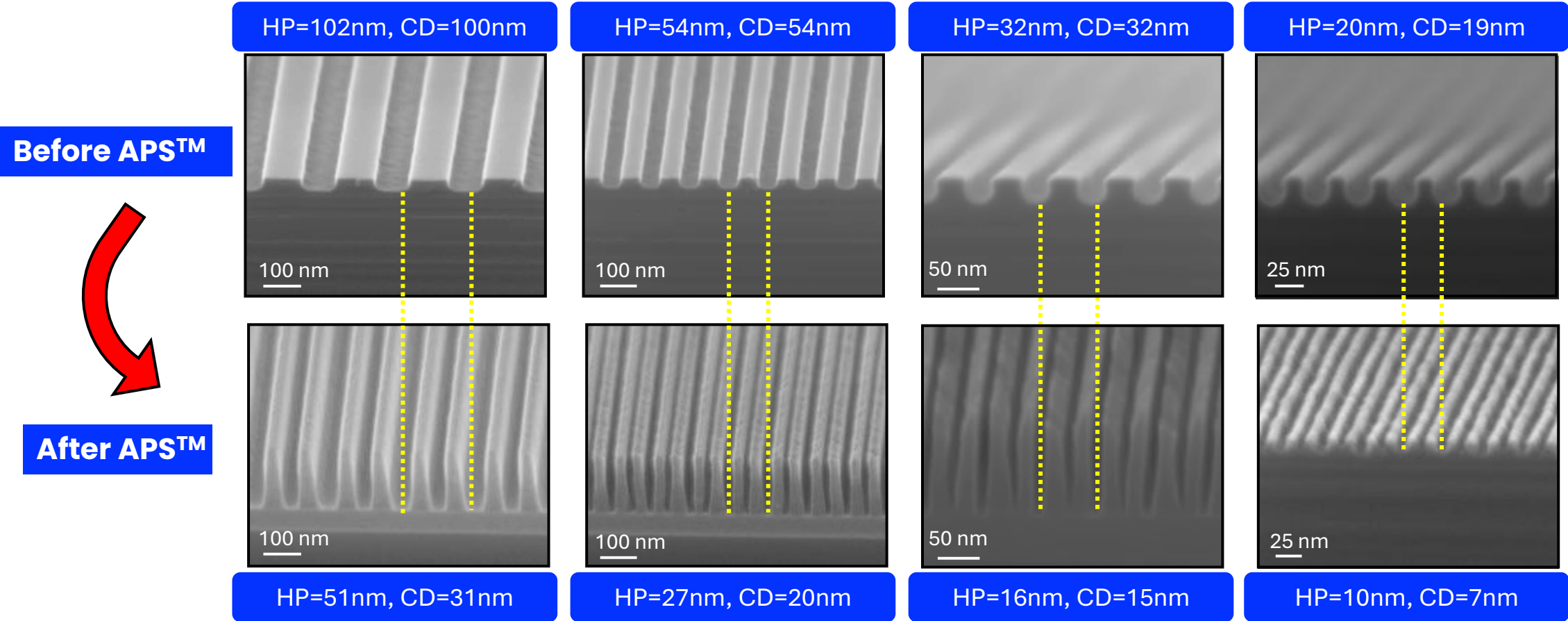


- APS™ simplifies pitch splitting with a single-step process, reducing cost, complexity, and environmental impact compared to SADP, which requires multiple deposition and etching steps
- APS™ enables higher yield, lower CAPEX/OPEX, and scalability to sub-2nm nodes

# APS™ on NIL-Defined SOI Wafer

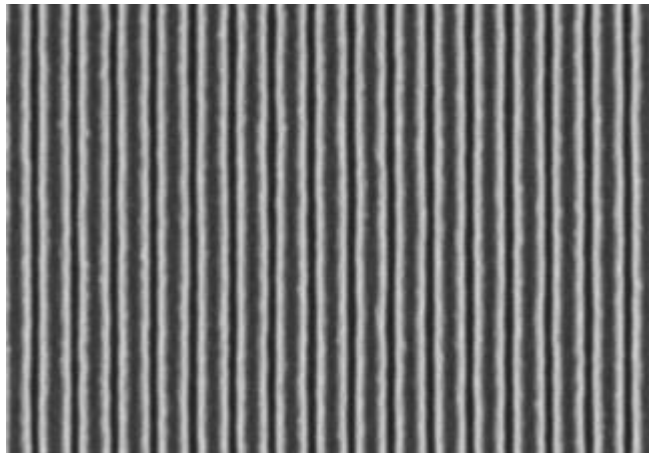


# APS™ on NIL-Defined SOI Wafer



# APS™ in Bulk Silicon vs Low and high NA EUVL in Resist

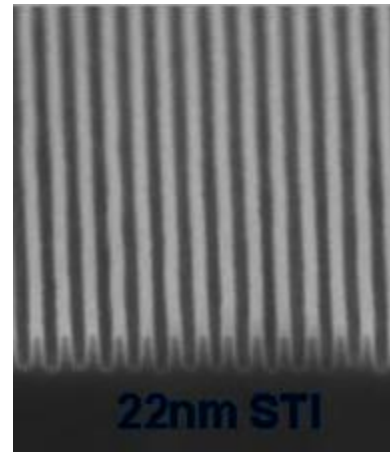
## NIL + APS™



CD	10 nm
Half Pitch	12.5 nm
LWR	2.2 nm
Material	Si

*This work*

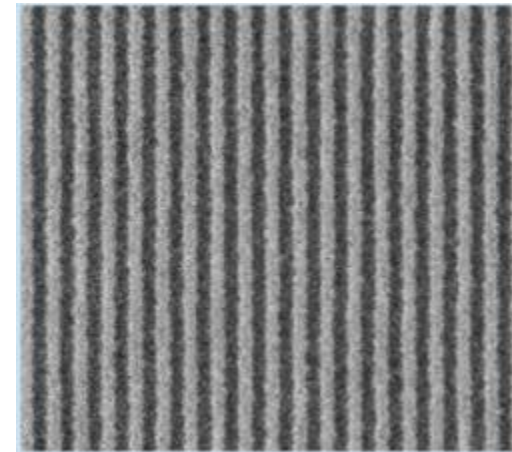
## ArF-i + SADP



CD	20 nm
Half Pitch	22 nm
LWR	2.5 nm
Material	Si

*Proc. SPIE, 69244E-12008*

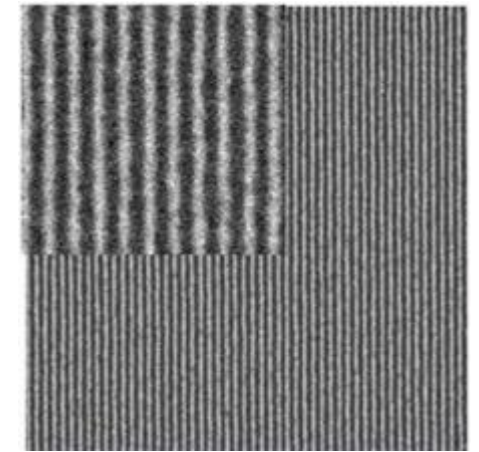
## Low NA EUVL



CD	12.7 nm
Half Pitch	12 nm
LWR	1.7 nm
Material	Resist

*EUVL Symposium, 11854-11 2021*

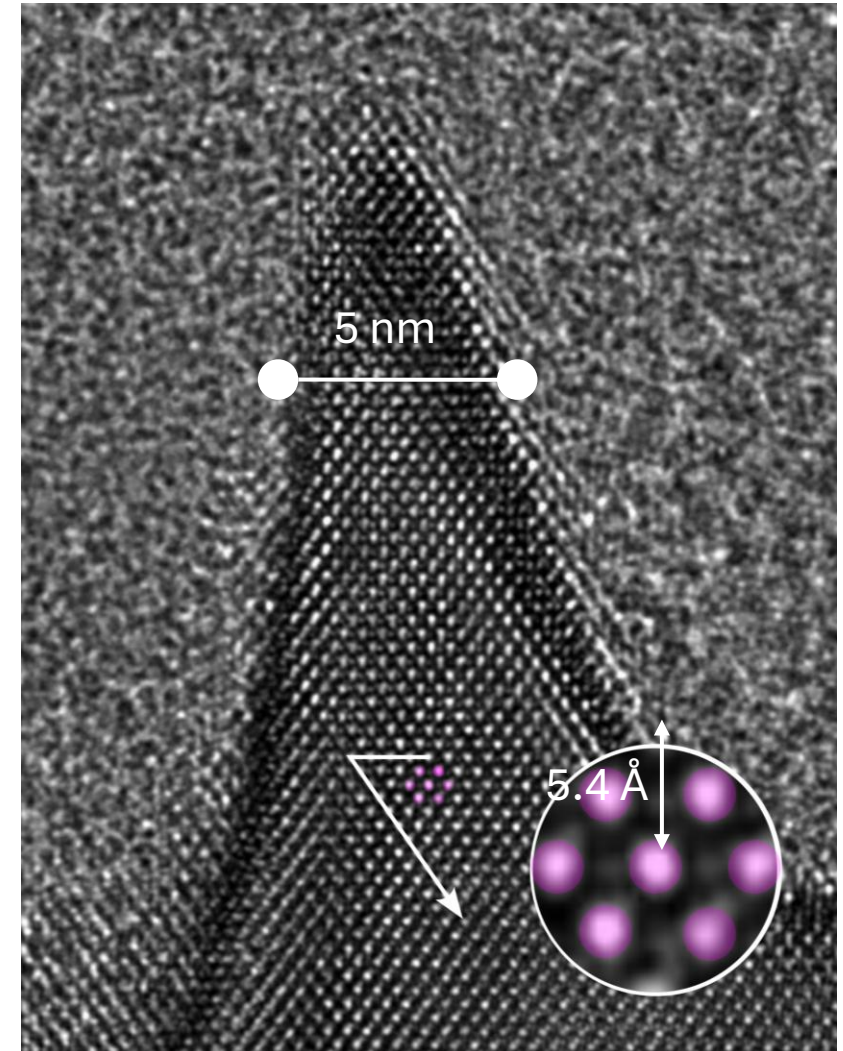
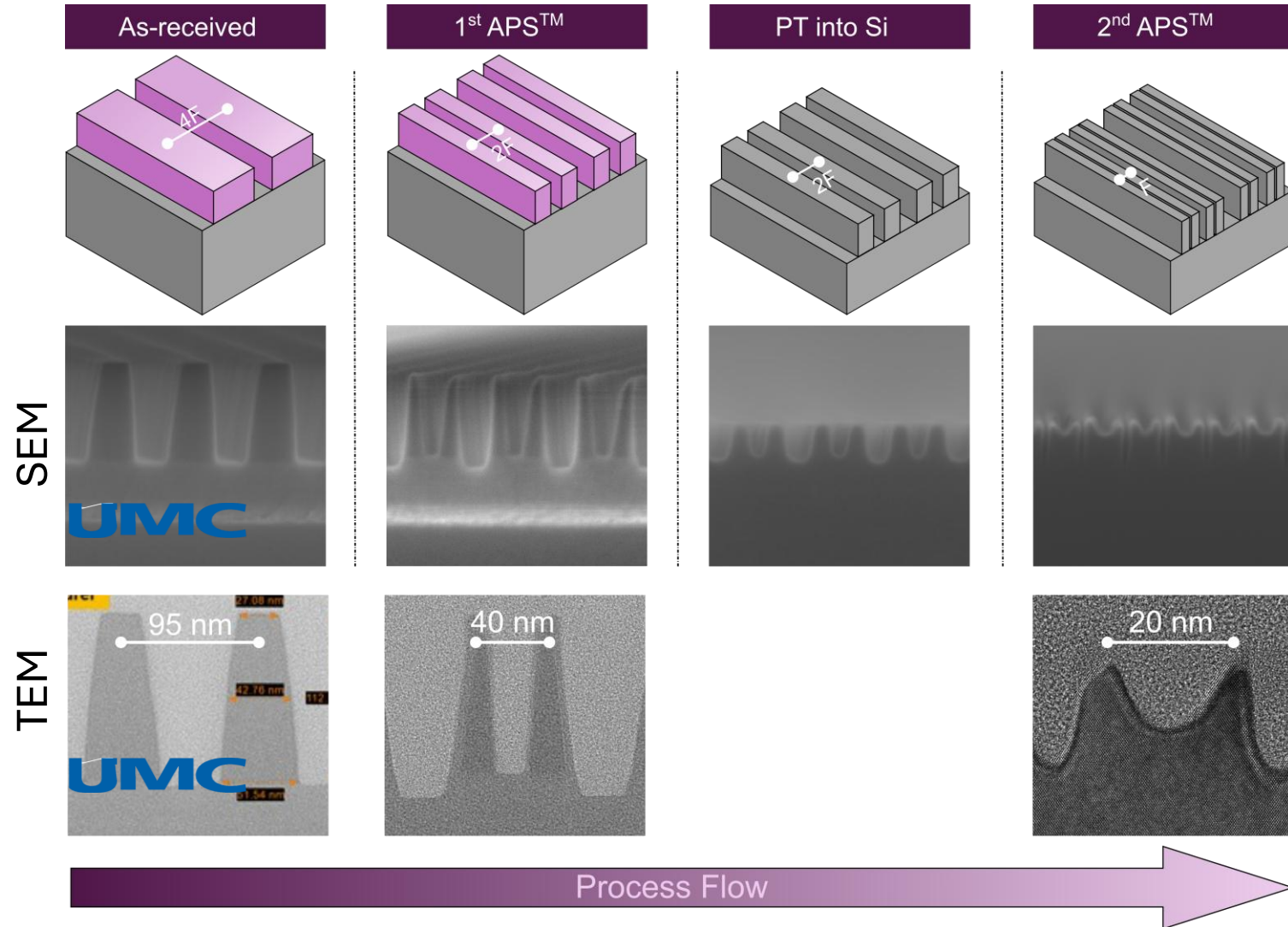
## High NA EUVL



CD	6.6 nm
Half Pitch	8 nm
LWR	2.4 nm
Material	Resist

*Source: Imec*

# Simplifying Quadruple Patterning by APS™



# AlixLabs APS™ & 300 mm ALE Equipment

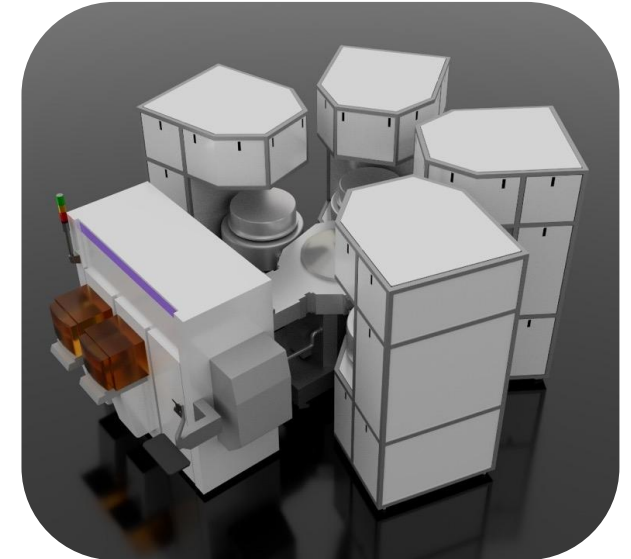
## Alpha APS™ Tool in AlixLabs Clean Room, Lund HQ



Alpha APS tool manufactured and operational in the AlixLabs Cleanroom in Lund, Sweden since 4Q/2024

First of a kind 300 mm APS tool for APS™ development and customer demonstrations

## AlixLabs Beta APS™ System Coming 4Q2026



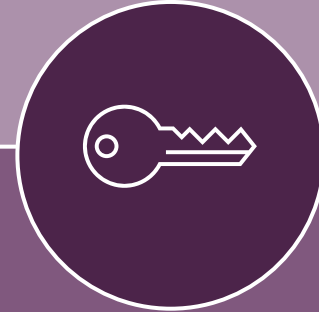
# Concluding Remarks



Costs and complexity in advanced nodes are largely driven by complex patterning processes



APST<sup>™</sup> offers a new approach of advancing process nodes without investing in new lithography



APST<sup>™</sup> can reduce cost and complexity while improving yield when compared to SADP and SAQP



Alix Labs strives to make fabrication more sustainable  
  
Join us today for a more sustainable future !



**Let's connect**

[alixlabs.com](http://alixlabs.com)  
[info@alixlabs.com](mailto:info@alixlabs.com)